## SUPPLEMENTARY MATERIAL

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Fig. S1 Scanning electron micrographs showing photoresist overburden removal by timed UV exposure (shown in seconds) for chevrons grown at  $\alpha = 85^{\circ}$  with noticeable overburden. Scale bar indicates 1  $\mu$ m.



Fig. S2 Scanning electron micrographs showing (a) side and (b) top views of the vertical post nanostructured thin film used for separating DNA. Scale bars indicate 1  $\mu$ m.



**Fig. S3** 10 kbp and 48 kbp DNA separation was highest at a frequency of  $\sim 2$  Hz and angle of 13.5°. Separation angles were measured 2 mm from the injection point. The error bars indicate upper and lower bound measurements of the separation angle.